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# Photonics Design Automation and MPW Runs for Affordable Chip Production

*design tools, design kits and collaboration*

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**PIC TRAINING NYC 2015**

COLUMBIA UNIVERSITY, NEW YORK, USA, OCTOBER 19-23 2015

TWAN KORTHORST

# Who we are

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## Lumerical Solutions

- HQ in Vancouver, Canada, since 2003
- Design software for photonic technologies
- Circuit and physical simulation tools



## Mentor Graphics

- HQ in Wilsonville (Or.), USA, since 1981
- Solutions for full flow custom design methodologies
- Leader in physical verification solutions



## PhoeniX Software

- HQ in Enschede, the Netherlands, since 2003
- Chip design for micro and nano technologies
- Physical simulation and layout generation



# Why integrated photonics?

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## Electronics market is mature

- Total electronic components markets is > 500B\$, with IC's ~250B\$
- Electronics Design Automation (EDA) market just under 10B\$

## Mature (silicon) electronics industry comes with

- Fabless business model dominant
- Good array of foundries (TSMC, GF, Jazz, IBM, etc.)
- Well developed EDA industry (Synopsys, Cadence, Mentor Graphics)

## Existing technologies are reaching bandwidth limitations

- Power consumption (heat) dominated by data transfer rather than computing
- Density

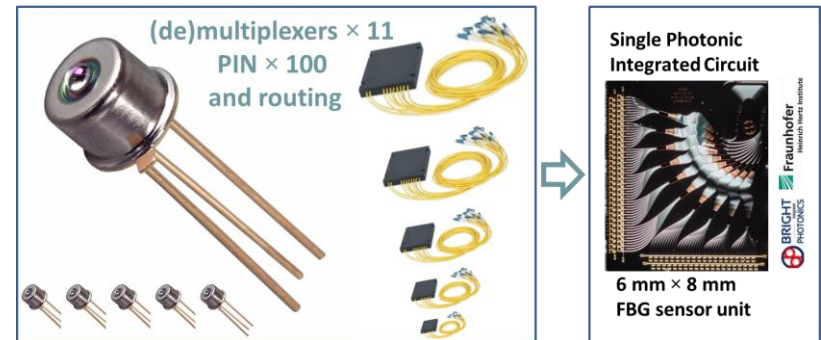
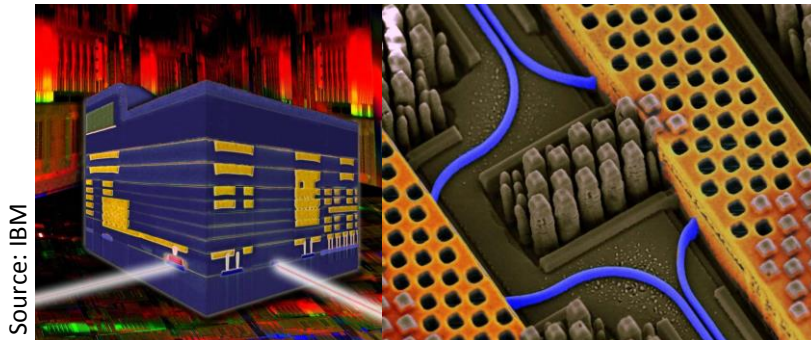
# 'Photons will merge with electrons'

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- **Market need drives transition to integrated photonics solutions**
  - Datacenters and High Performance Computing
  - 40G/100G/400G, FTTH
  - Microwave photonics (5G, nextgen wifi, LiDAR, ...)
  - (Bio-)sensing
- **Photonic Integrated Circuit market today relatively small (220M\$)**
  - Market size x4 by 2019, still only 0,4% of global IC market size
  - Today mainly InP based, performance driven
- **Integrated photonics enables the transition by leveraging IC manufacturing technologies**
  - Cost effective manufacturing (in volume)
  - Functions integration
  - High density
- **Photonics technology is considered to be strategically important**
  - Multiple Billion\$ value in 'transactions & investments' recently
  - Photonics will become a significant part of the electronic IC market

# There are many similarities between electronics and photonics

- Fabrication: thin film technologies, lithography
- Design flow: verified mask layout design as final step
- Photonics is where electronics was in the 80's
  - Transition from PCB to (silicon) IC
  - Large number of (small) fabs providing manufacturing capacity
  - Many software suppliers, each covering parts of the design flow
  - Emerging standardization in processes and tools

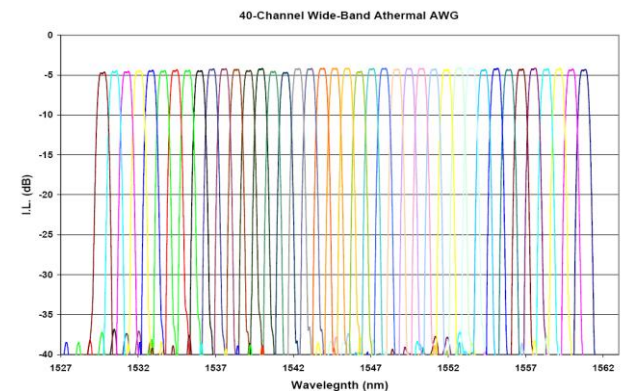


# With some key differences

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## Photonics industry today is dynamic and fragmented

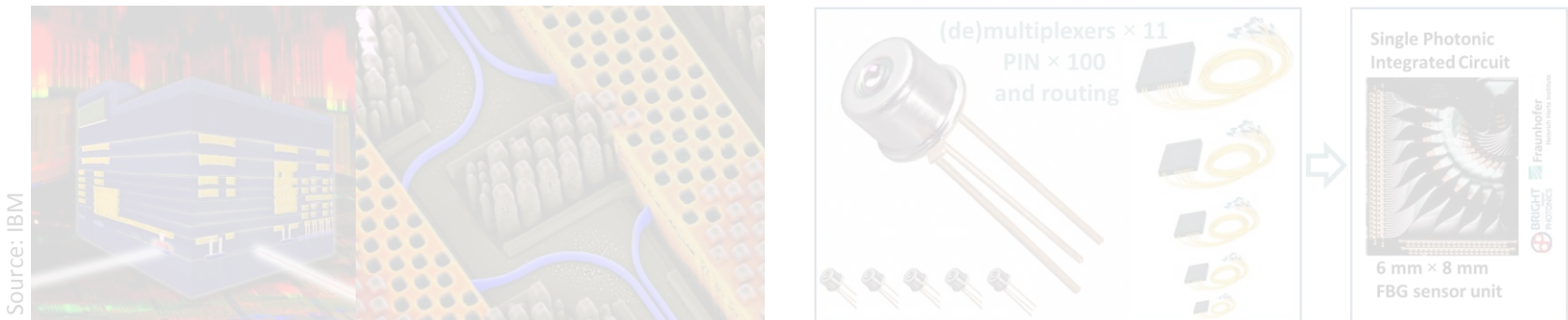
- Wide variety of materials and technologies
  - Si / SOI, InP / III-V, PLC, TriPleX / SiN, LiNbO3, Polymers, ...
  - Hybrids, 3D stacking, SiP
- Scalability roadmap is unknown
  - Typical line-widths: 0.15 – 4 micrometer
  - Number of components: 10's – 1000's per chip (relates to 10k – 1M primitives)
- RF-like or analog behavior (Telecom C-band is 1530 – 1565 nm ~ 193 THz)
  - Design closely related with fabrication
  - Process and temperature dependencies



Source: Kalam

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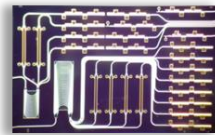


# If you need a PIC, where do you go?

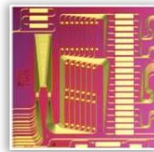
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- You need an application specific PIC

**Fiber to the Home  
Wireless**



**Medical  
Bio-imaging**



**Datacom  
Switching**



**Sensor  
Readouts**



*Please note that electronic ICs have paved the road for 50 years*

- You need to decide on material and foundry
  - Options: InP, Silicon, or TriPleX (excluding PLC and LiNbO3)
- Also need to decide on MPW vs. a custom run
  - MPW reduces costs, but custom runs might be needed in the end (for volume and/or for unique performance)



# Decide on material

## Active materials (lasers...) only possible in InP



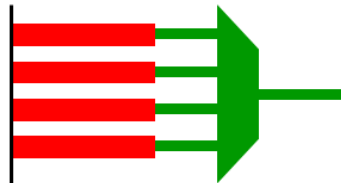
SOA



Fabry-Perot lasers



Tunable DBR lasers



Multiwavelength lasers



Picosecond pulse laser

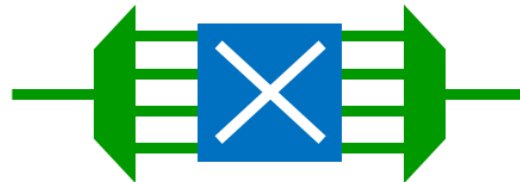
## Switches & modulators possible in InP & Silicon



Phase modulator



Amplitude modulator

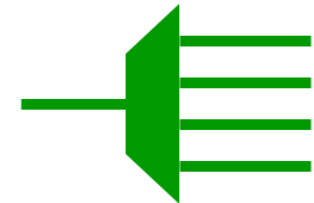


WDM crossconnect  
WDM add-drop

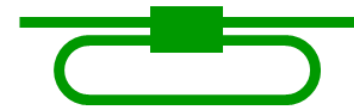
## Passives possible in InP, Silicon, and TriPlex



MMI-couplers  
MMI reflectors



AWG-demux



Ring filters



Thermo optic  
phase modulator

# Decide on foundry

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## Multi Project Wafer runs versus Custom runs

- **MPW users all share the same generic fabrication process**
  - Cost sharing: multiple designs at same mask/wafer
  - Imposes limits, but comes with a library of building blocks
  - “Lego” building blocks allow for virtually all PICs
  - >500 PICs developed in generic fabs via MPW runs
- **There are several key players, mainly in Europe:**
  - Silicon photonics: CEA-Leti, IHP, IME, IMEC, VTT
  - InP: FhG/HHI, Oclaro, SMART Photonics
  - TriPleX (SiN): LioniX
  - AIM Photonics won the IP-IMI award in the US
  - And ... don't forget about packaging



# Decide on foundry

## Foundry platforms - overview

Broker	Process	Lasers	SOAs	TDBR	Modulators / Phase shifters				Detectors			Prop loss dB/cm
					L (mm)	V <sub>p</sub> - P <sub>p</sub>	Loss (dB)	B (GHz)	R (A/W)	B (GHz)	I <sub>dark</sub> (nA)	
JePPIX	Oclaro TxRx 10G	YES	YES	YES	1	3.5	< 2	> 10	0.8	10		2-3
JePPIX	HHI Tx- Rx 25G	YES	YES	YES	0.5	(25 mW)	< 2	(kHz)	0.8	40	< 10	1-2
JePPIX	SMART TxRx 10G	YES	YES		2	7	< 2	10	0.8	10	< 20	3-4
JePPIX	TriPleX (DS-500-170)				1-2	(500 mW)	< 0.1	(kHz)				< 0.5
VTT	VTT 3 μm SOI				1		< 0.1	(kHz)				0.1-0.15
Europractice	Imec ISIPP25G+				1.5	7	6	20	0.5	> 50	< 50	1.5-2.5
					0.04*	2*	5*	>50*				
Europractice	CEA-LETI Si310-PHMP2M				1 - 4	< 7.5	<2.5	< 12	0,7	30	< 10	< 2.5
Europractice	IHP											

\*Germanium electro absorption modulators

- TriPleX and VTT 3 μm SOI have the lowest losses. TriPleX is also suitable for visible light
- For active components with gain and lasers, only InP can be used
- Silicon for high integration density, reproducibility and volume scalability

6<sup>th</sup> European Photonic Integration Forum

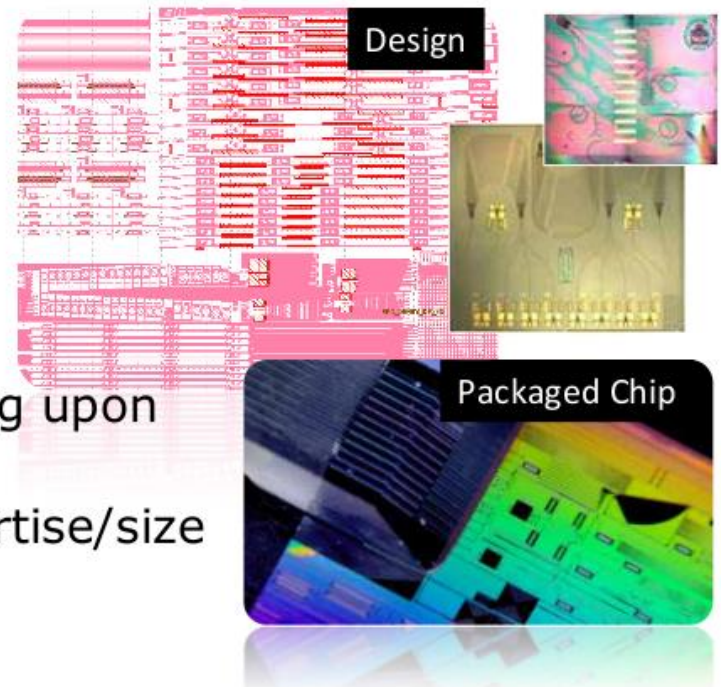
# Typical timelines

## Photonic MPW Development Cycle

- Concept to Design Phase (1-3M)
- Fabrication cycle (2-6M)
- Packaging (1M)
- Testing (1-2M)

Second Iteration (5-10M) depending upon

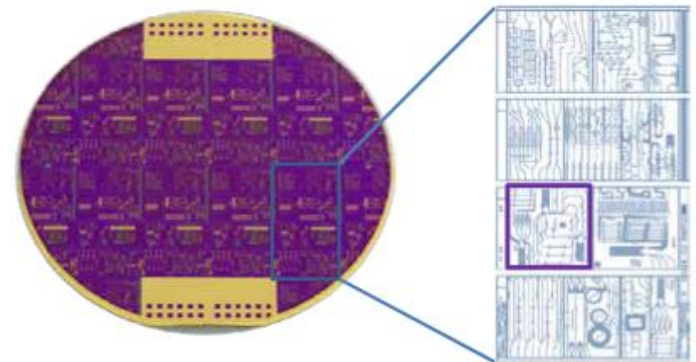
1. Technology complexity
2. Product development team expertise/size
3. Design experience



# Rules of engagement

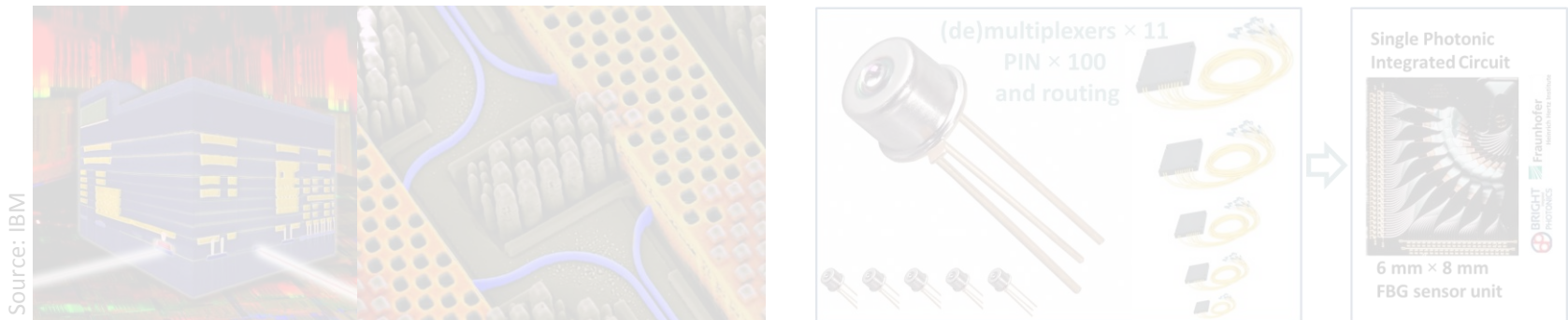
## How to get access?

1. Sign user agreement: NDA
2. Get access to Design Manual and PDK
3. Reserve a cell in one of the MPWs
4. Design using PDK: implemented in software tools
5. Get design support from Design Houses or design by yourself (PIC training recommended)
6. Send in your design on time



# There are many similarities between electronics and photonics

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# PIC Design Software

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- Today really good design solutions are available
  - Electronics Design Automation (EDA) made for Electronic ICs
  - Likewise, Photonic Design Automation (PDA) being created for PICs
- **But there are in between situations:**
  - What if your chip has optical as well as electrical components?
  - What if you plan to do the photonic simulations in PDA, but then use EDA for the mask layout?
  - And, there are ongoing efforts between EDA and PDA providers to make their S/W interoperable and support the industry to scale from R&D to (volume) manufacturing
- Even though some functions can be done using both PDA as well as EDA, some care is needed...

# EDA and PDA: photonics $\neq$ CMOS

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## Digital IC design flow

Specification

System Design

Circuit Design = Auto-generated

System Simulations

Circuit Layout = Auto-generated

Top-level = Auto-routed

Verification

Manufacturing

## RF-IC & Photonics design flow

Specification

System Design

Circuit Design

Component Design

Circuit Simulations

Worst-Case Circuit Simulations

System Simulations

Worst-Case System Simulations

Circuit Layout Design

Top-Level Layout/Interconnect

Verification

Manufacturing



# EDA and PDA: photonics $\neq$ CMOS

## Analog design time syndrome

“for a 10% analog 90% digital IC, the analog design takes 90% of the design time”

System Design

Circuit Design = **Auto-generated**

System Simulations

Circuit Layout = **Auto-generated**

Top-level = **Auto-routed**

Verification

Manufacturing

Circuit Design

Component Design

Circuit Simulations

Worst-Case Circuit Simulations

System Simulations

Worst-Case System Simulations

Circuit Layout Design

Top-Level Layout/Interconnect

Verification

Manufacturing

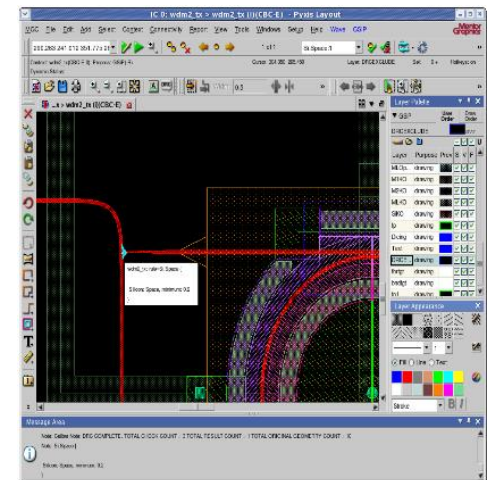
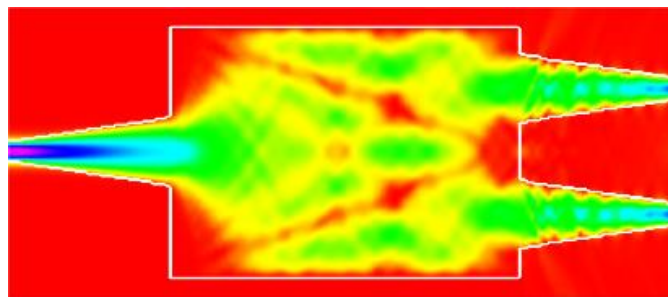
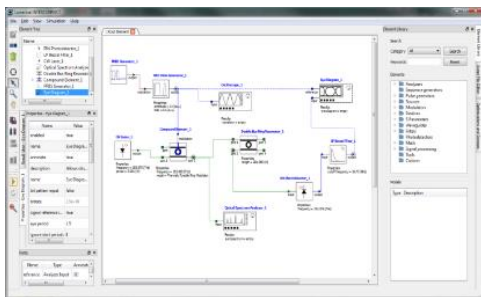
# Integrated Photonics Design

## Requires for simulations:

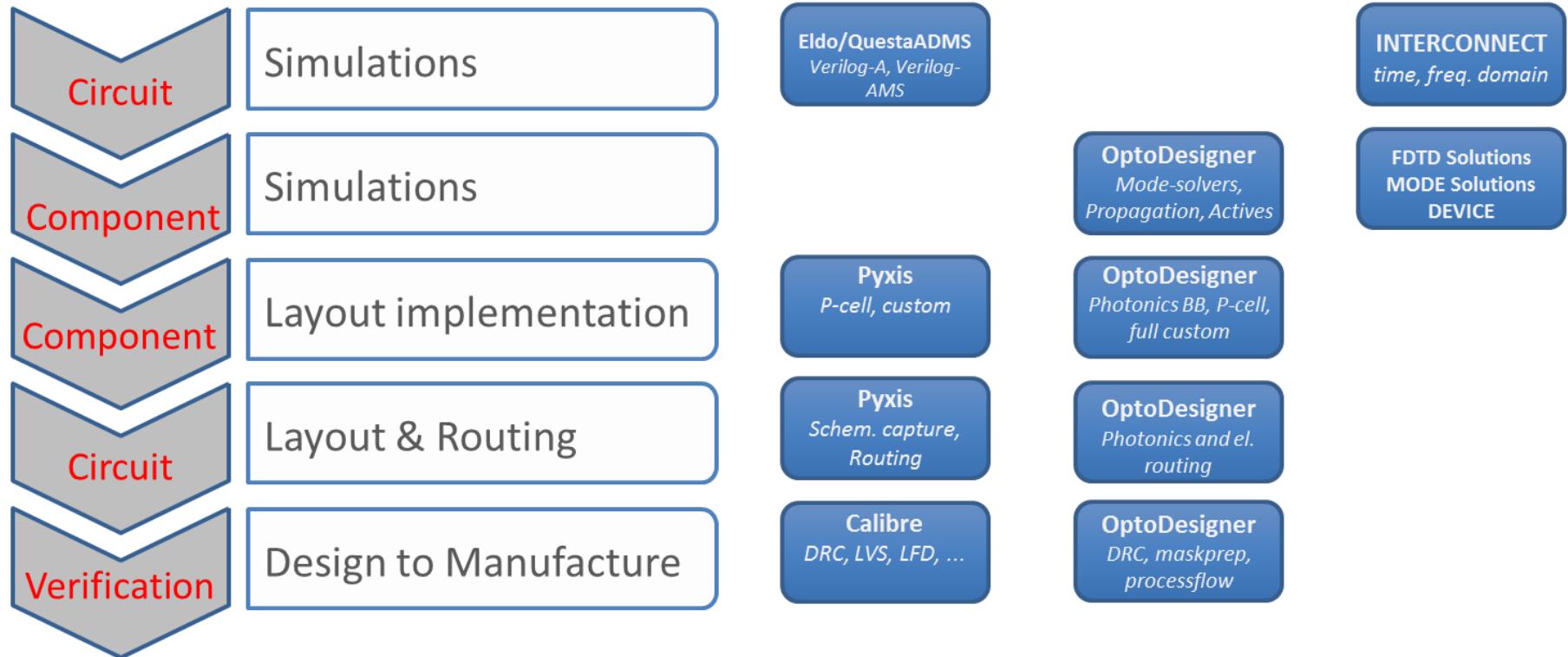
- Dedicated photonic circuit simulation tools
- Special physical simulation tools for integrated photonics
- Interaction between electronics and photonics

## Requires for mask layout:

- Accurate and flexible definition of all angle shapes
- Advanced gridding and fracturing of polygons
- P-cell like definition for primitives and compounds
- Special features for verification (DRC, LVS)

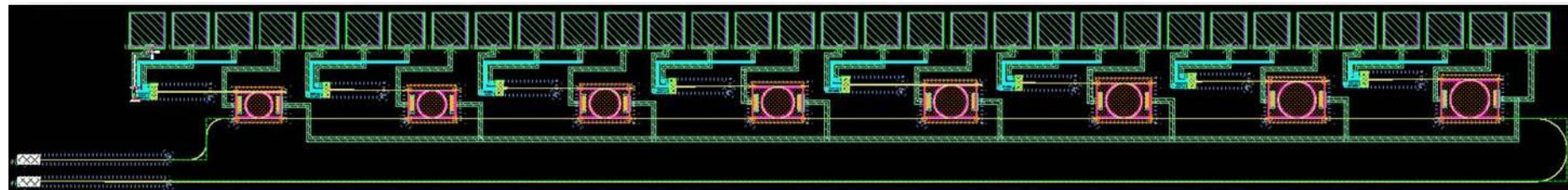
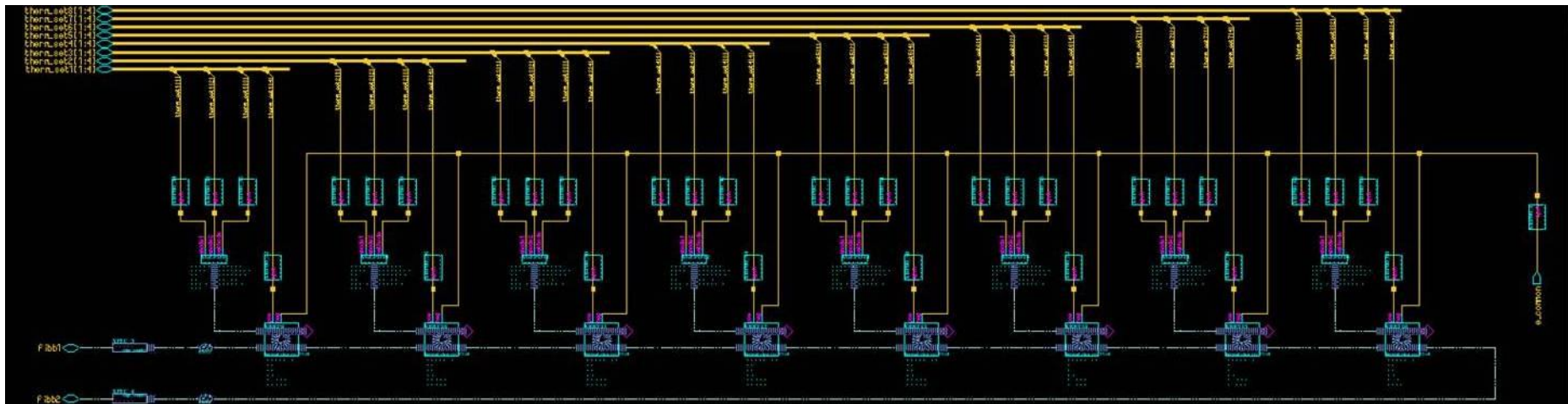


# Tools available for full flow



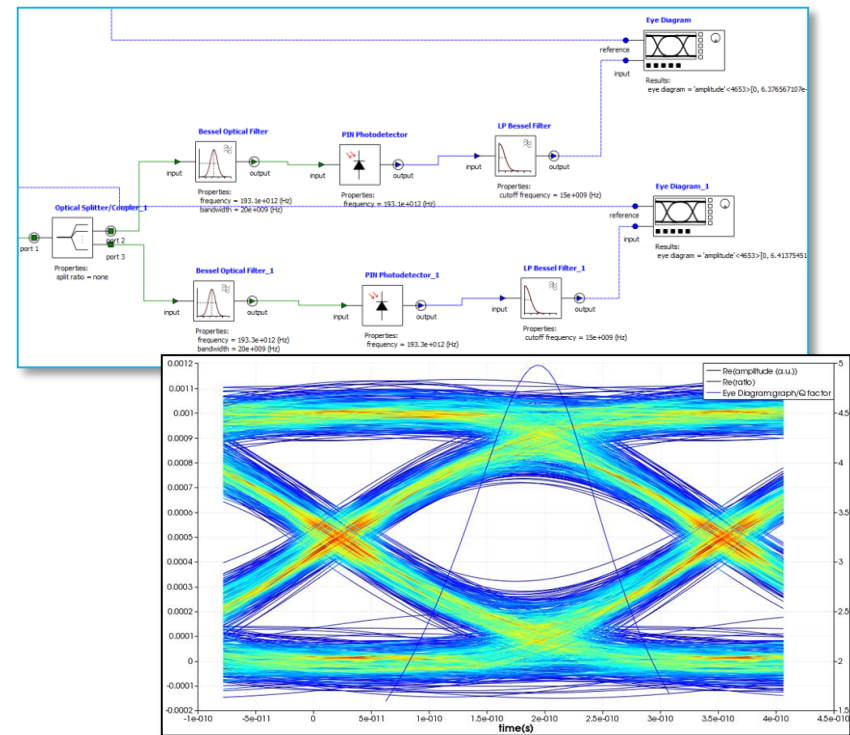
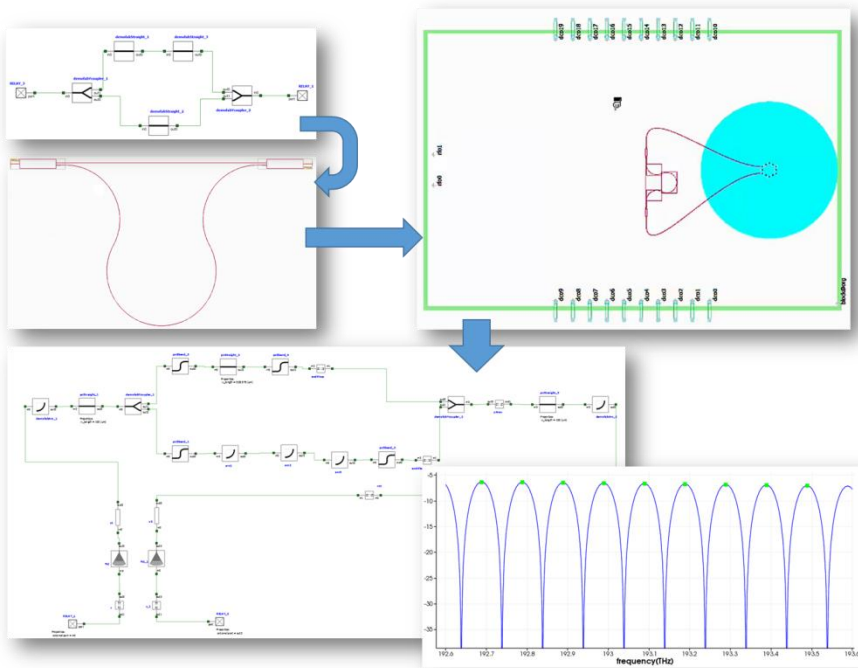
# Tools support circuit design

- Pick, place and connect validated components
- Photonic and electrical connections automatically detected
- Schematic connectivity will drive layout directly

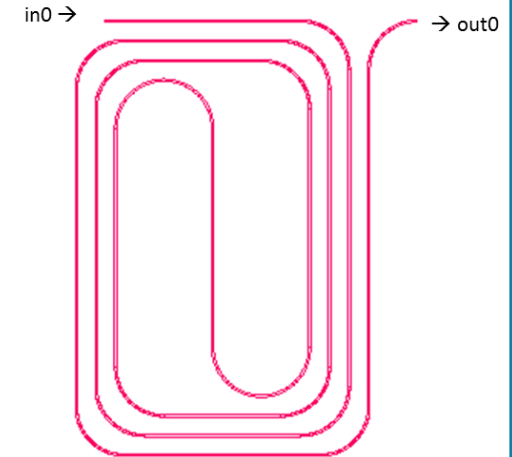
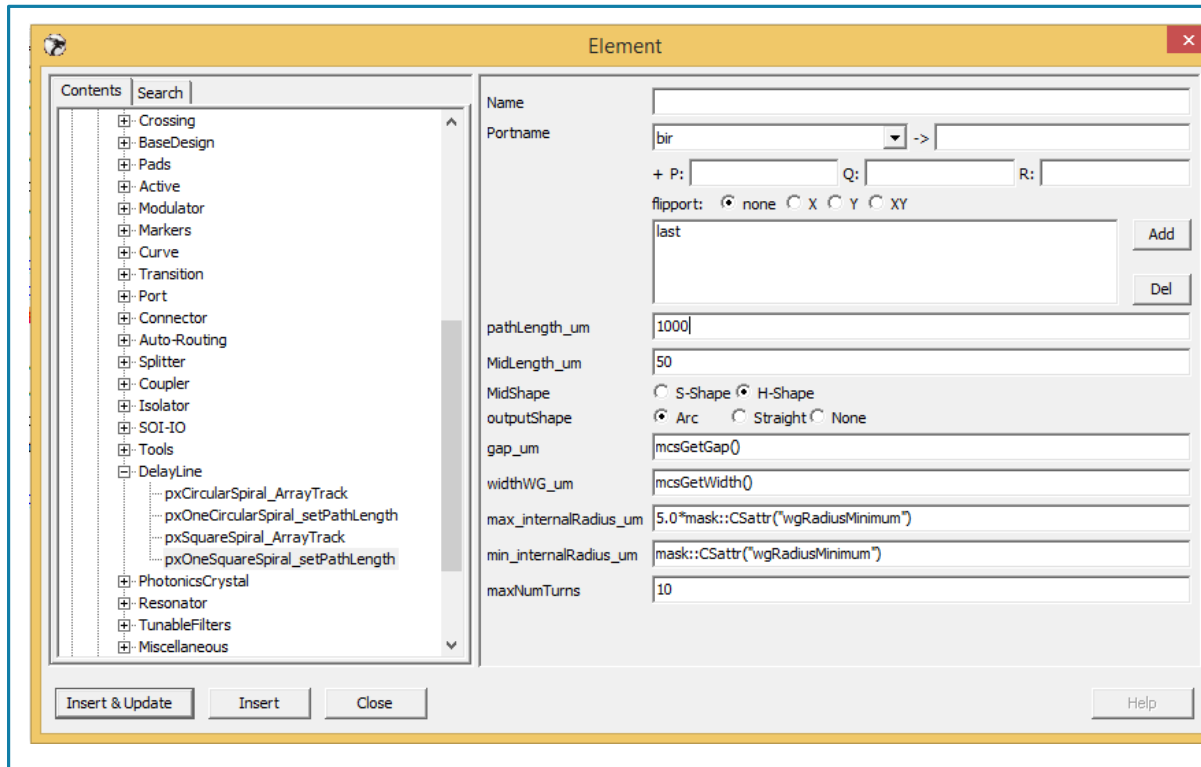


# Tools support circuit simulations

- Calibrated model libraries improve design accuracy
  - Design using compact model libraries of fundamental and complex devices, calibrated to foundry processes
  - Frequency & time domain simulation

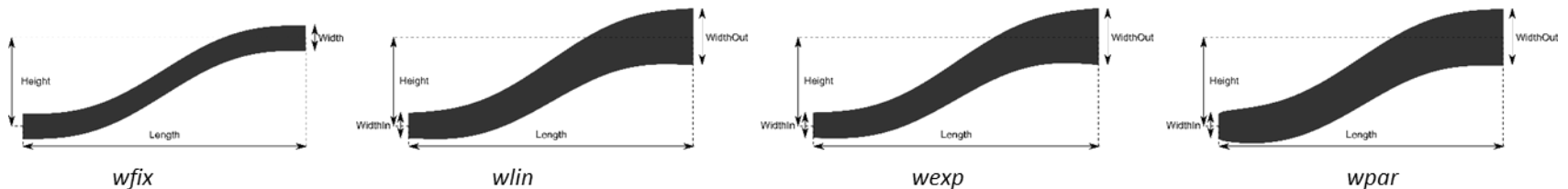


# Tools support component design



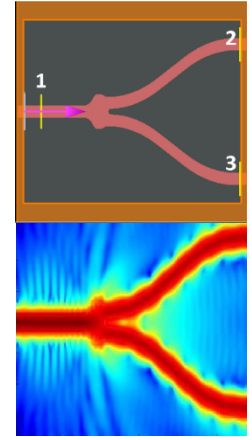
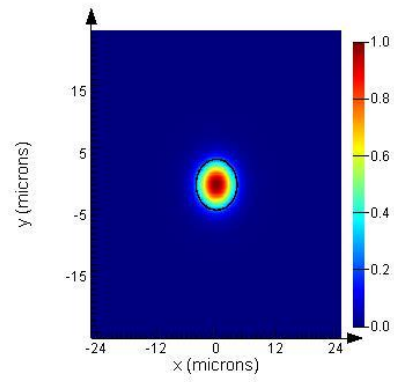
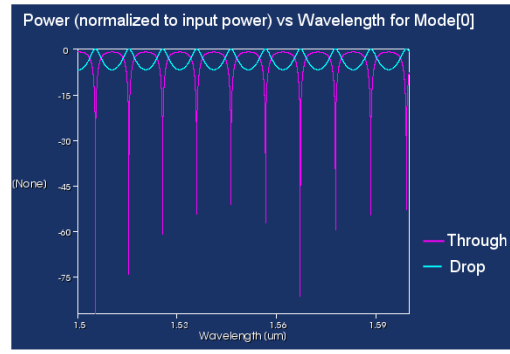
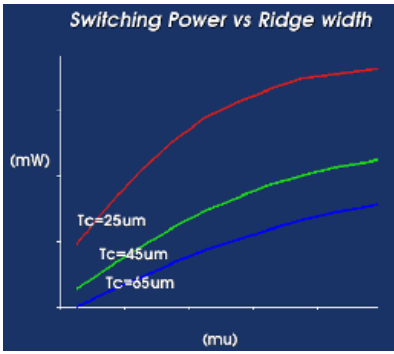
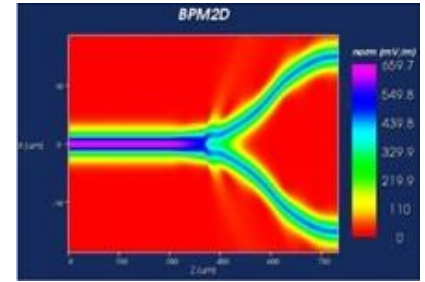
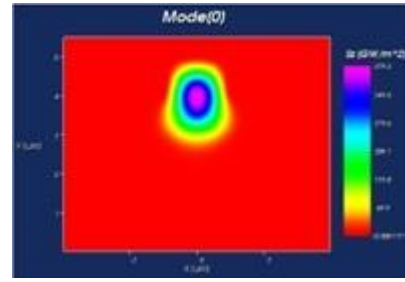
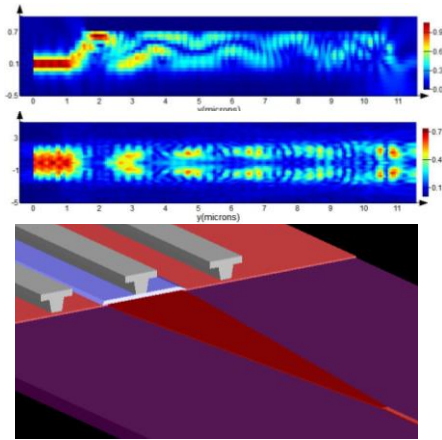
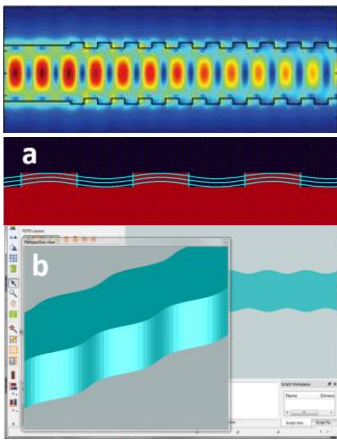
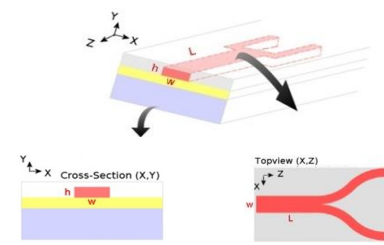
Spiral delay-line, defined by either geometrical or optical parameters

Wide variety of layout primitives available to design custom components, like a parametrized sine-bend



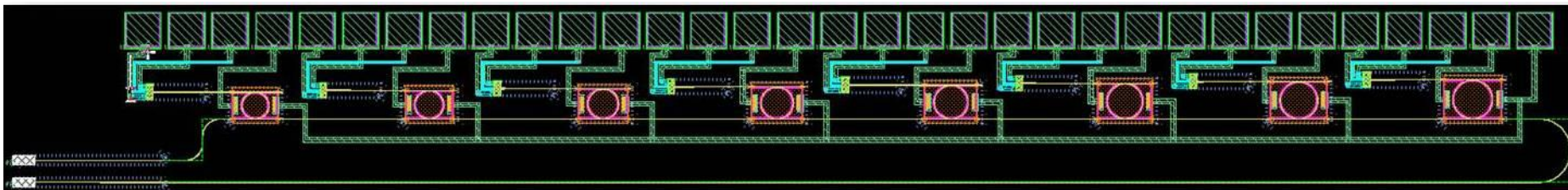
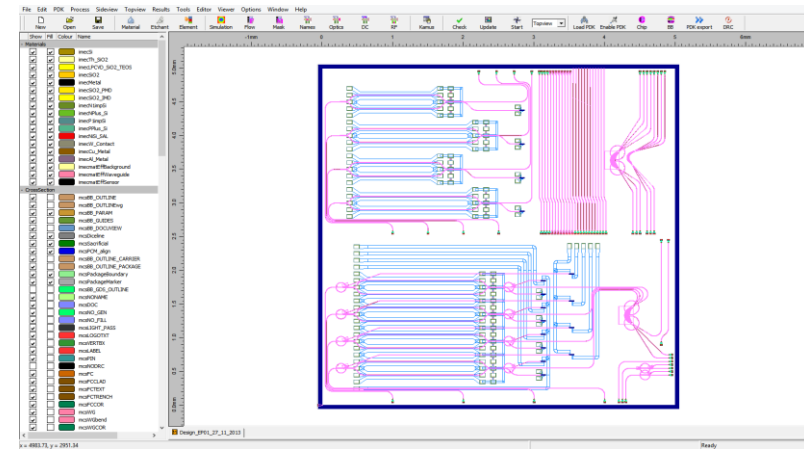
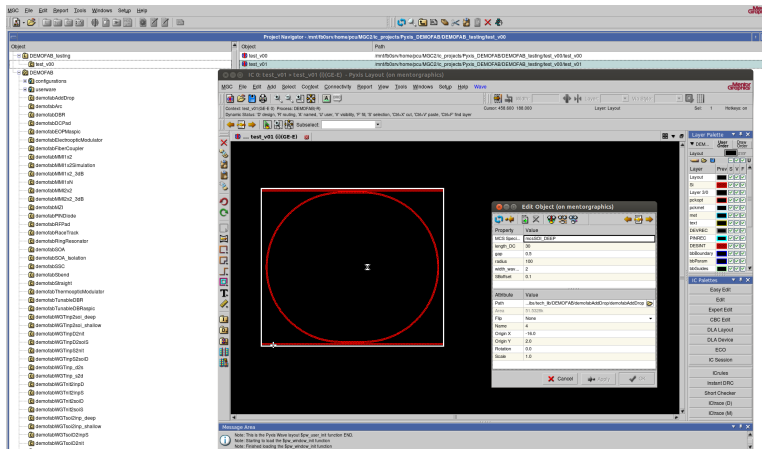
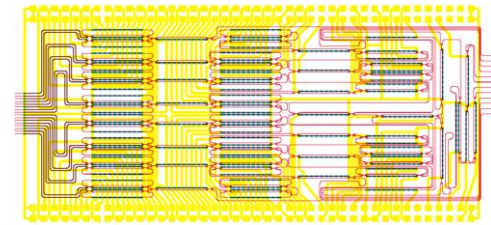
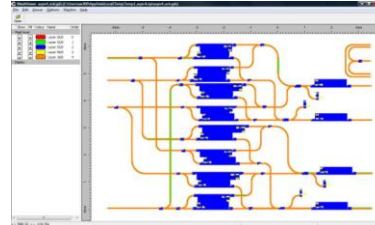
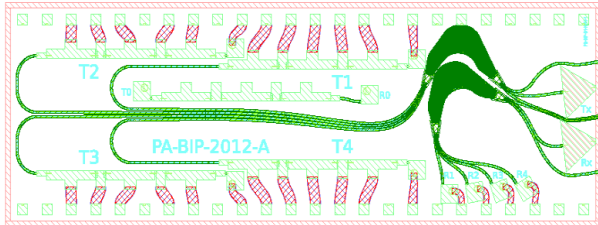
# Tools support component simulations

- Propagation simulations: eg. FDTD, EME, BPM
- Mode simulations: eg. mode-solvers, CMT



# Tools support circuit mask layout

- Pick, place and route or schematic driven layout

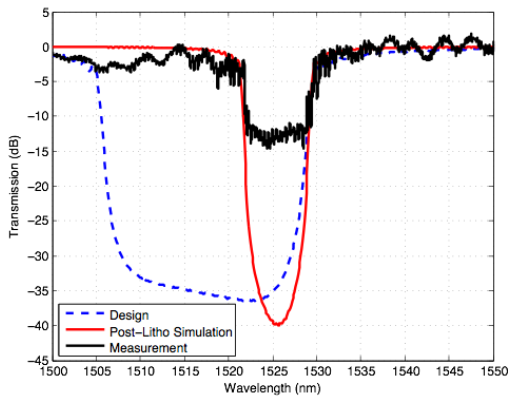




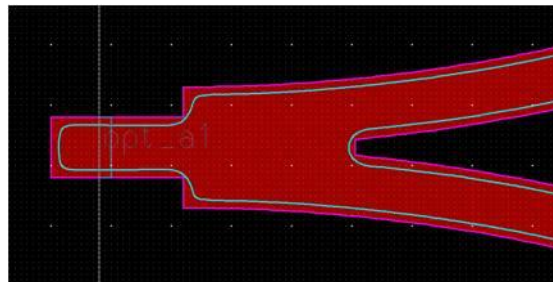
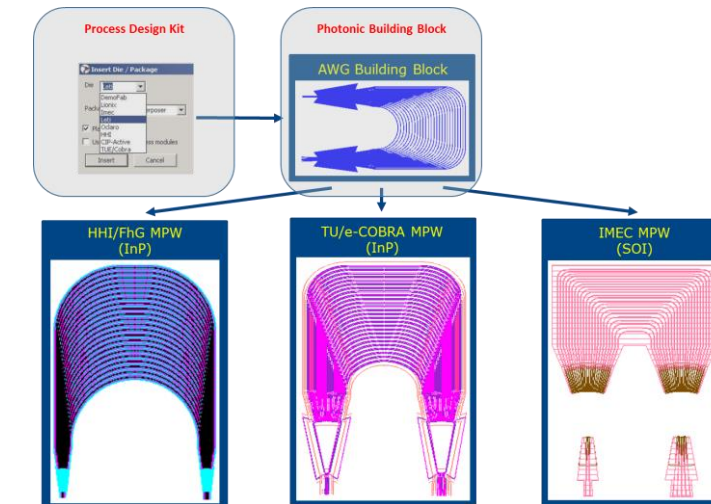
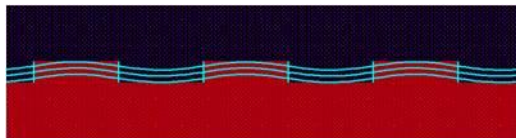
# Tools support mask layout

- Design software can translate design intent into layout
- ... and correct for process influences

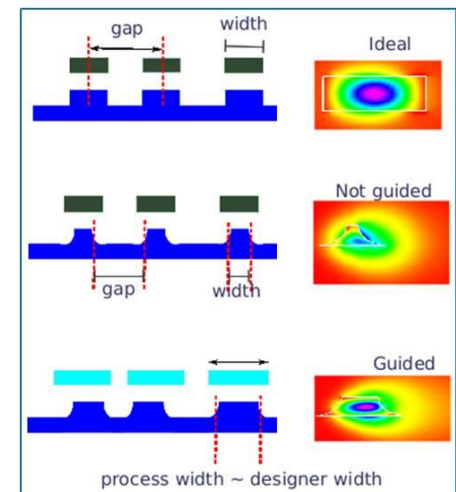
*Simulating lithography influence on design intent*



Xu Wang, et al., "Lithography Simulation for the Fabrication of Silicon Photonic Devices with Deep-Ultraviolet Lithography", IEEE GFP, 2012

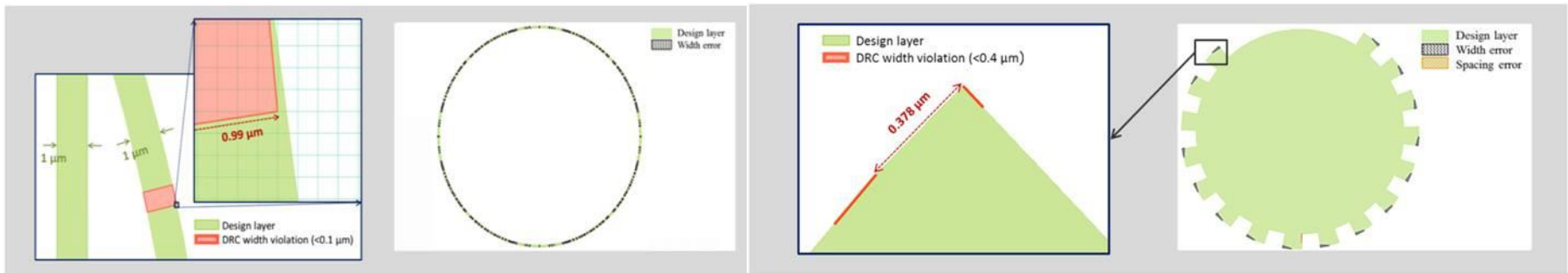
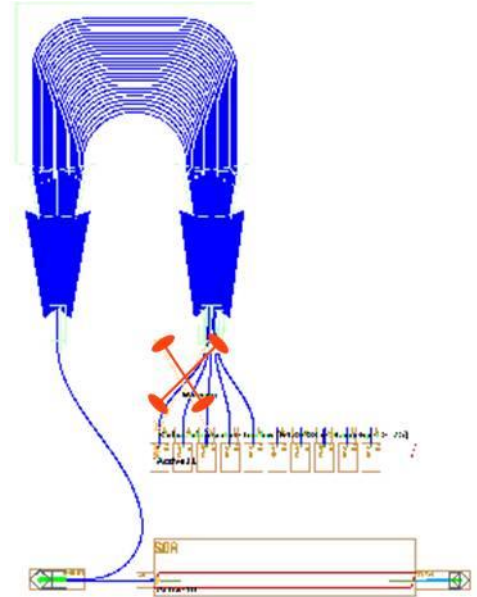


*Use technology information to obtain design intent after fabrication*

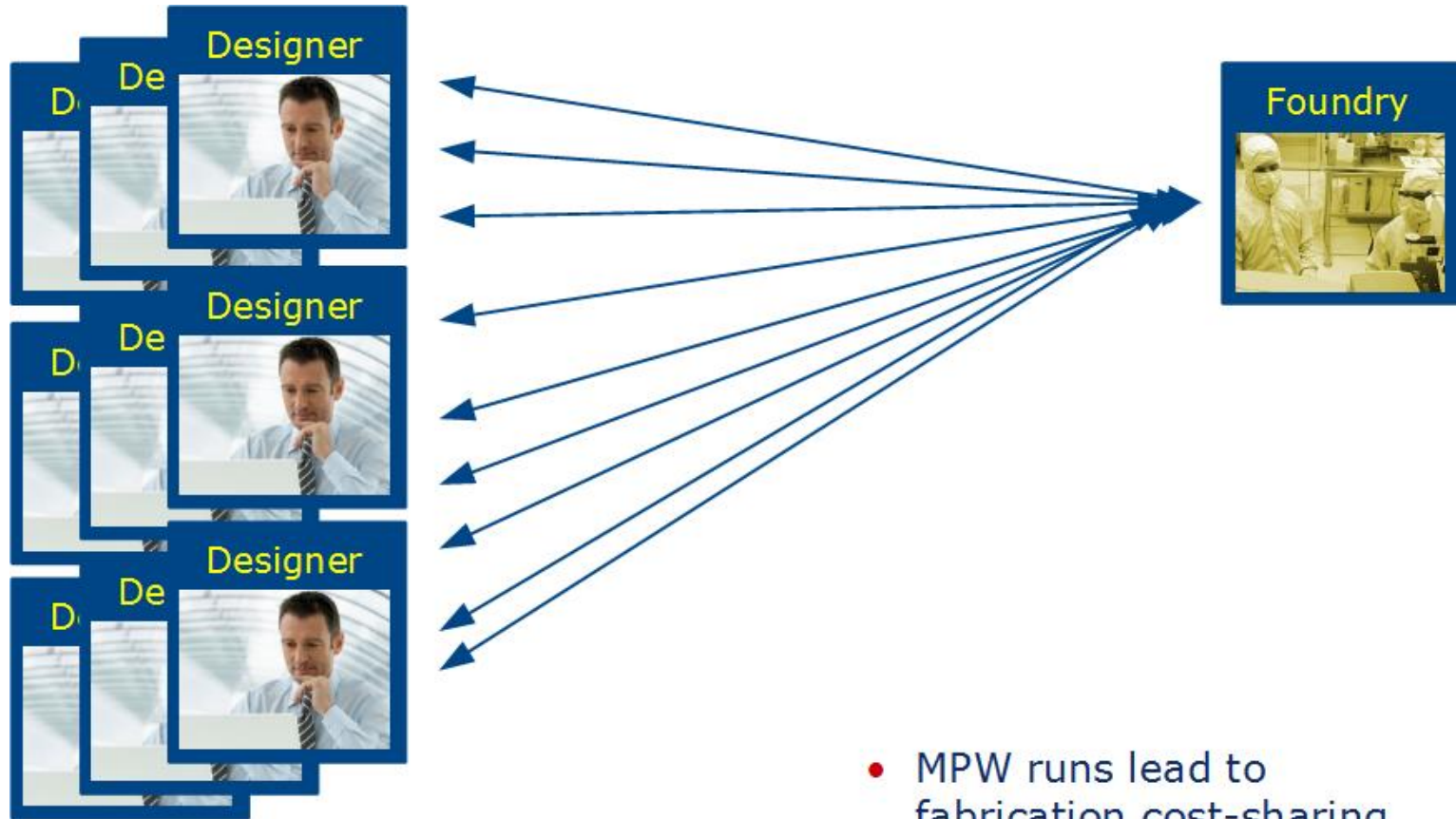


# Tools support verification

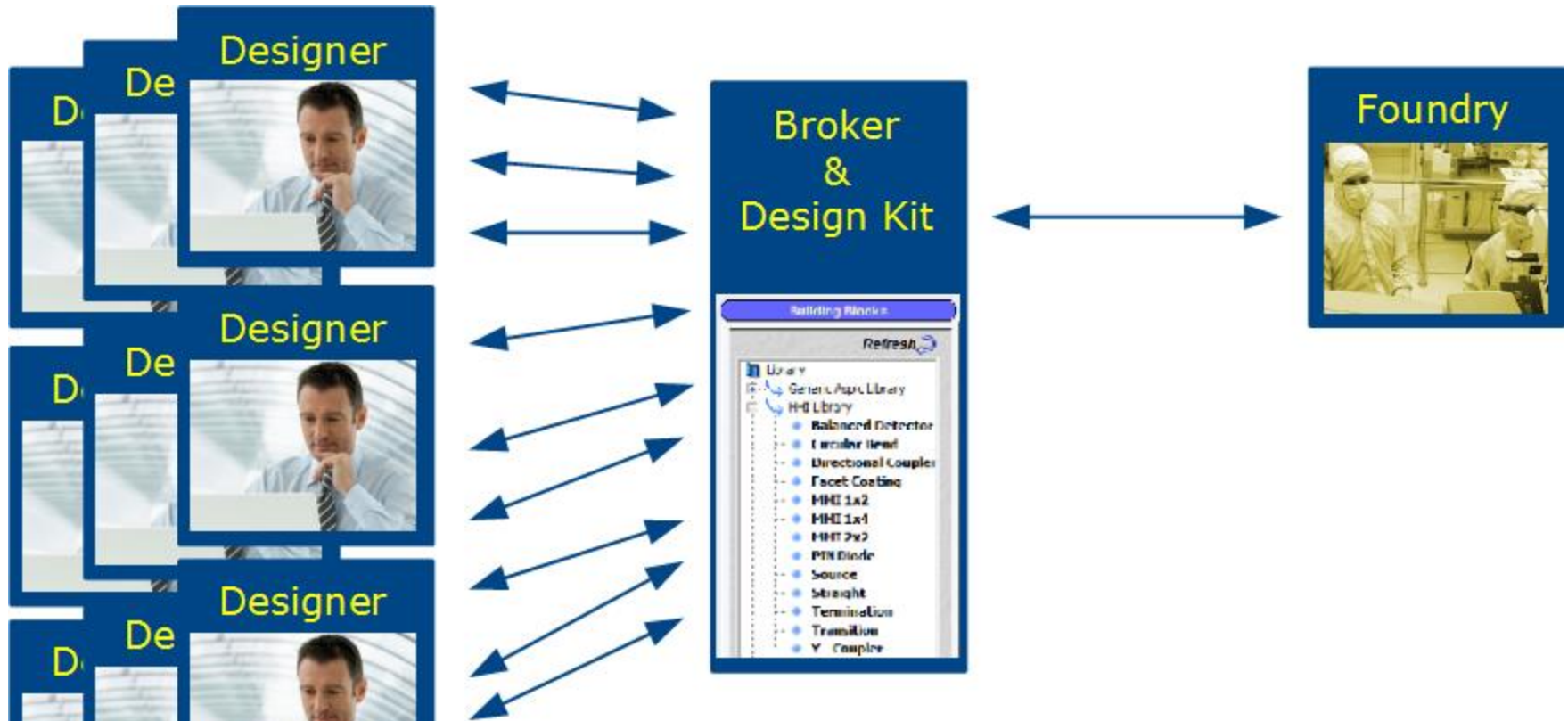
- Functional verification, Design Rule Checking (DRC) and Layout vs Schematic (LVS)
- Built-in photonics relevant design checks (like minimum bend radius)
- Design rules targeting CMOS processes will flag thousands of false errors in photonic structures, Photonic specific DRC rules can minimize false errors
- Integrated design flows enable LVS



# Why are PDKs so important?



# Why are PDKs so important?



- Design Kits lead to knowledge sharing and a decreased design effort

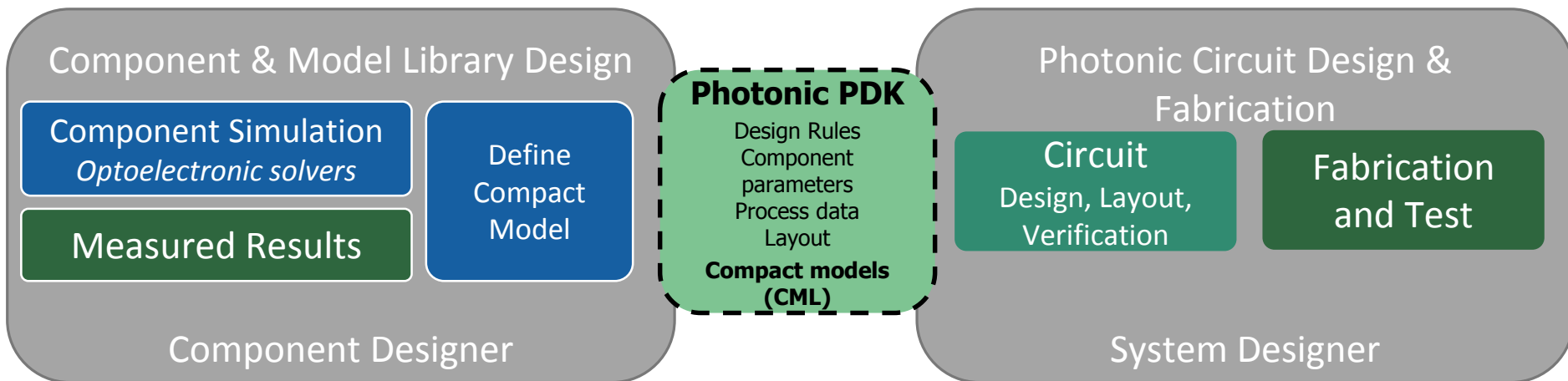
# Why are PDKs so important?

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- When working with a foundry (or your own fab), you do not want to reinvent the wheel nor make unnecessary mistakes
  - So all relevant knowledge should be available when designing a PIC
  - And the PDK should be automated (rather than in the form of docs)
  - Without a PDK, there are simply too many unneeded iterations
- What does a PDK include?
  - Design rules and mask layer information
  - Library of validated components
  - Layout information
  - Simulation models and settings
  - Die and package templates

# PDKs enable efficient development

- Faster design cycles and first-time-right designs
  - Higher accuracy by using validated compact model libraries for circuit design
  - Faster layout implementation by using predefined parametric components
  - Higher yield in manufacturing by applying design rules



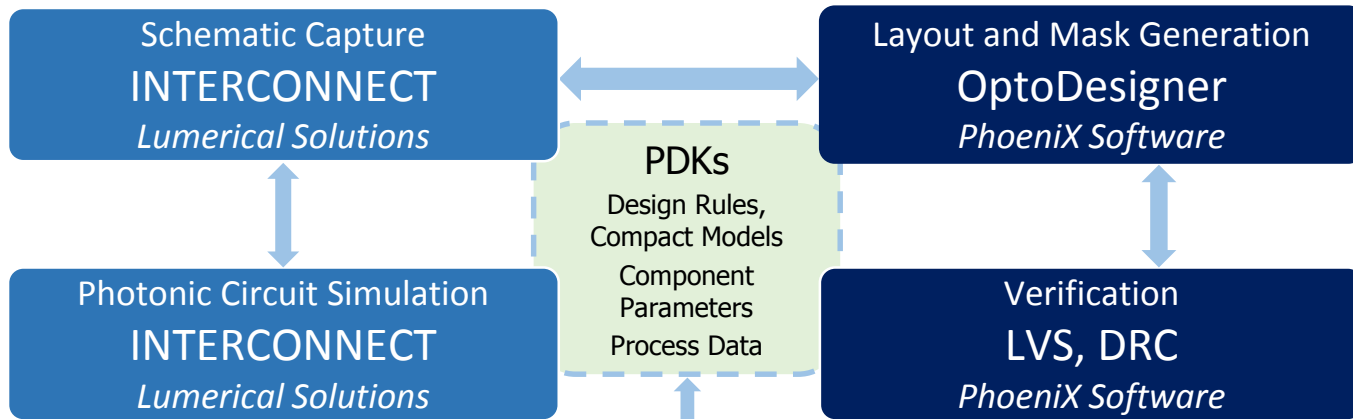
# A wide variety of PDKs is available

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- Foundries:
  - Silicon: IMEC, CEA-Leti, VTT, IHP and IME
  - InP: FhG/HHI, Oclaro and SMART Photonics
  - TriPleX (SiN): LioniX
- Packaging: Technobis ippis, Chiral Photonics, Gooch and Housego, Linkra, XiO Photonics and Tyndall
- PDKs are available to a varying degree of maturity
- PDKs are typically made available through MPW brokers



# PDKs support integration of design flows



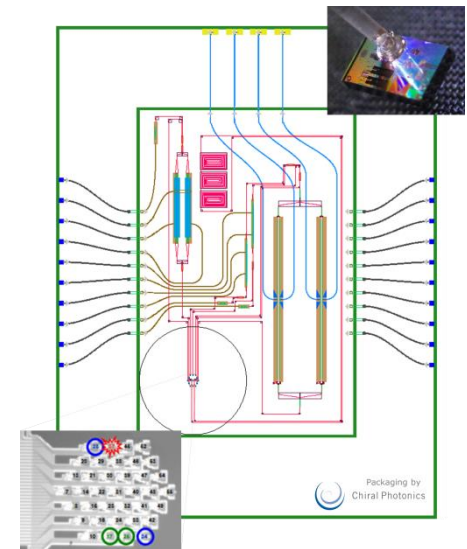
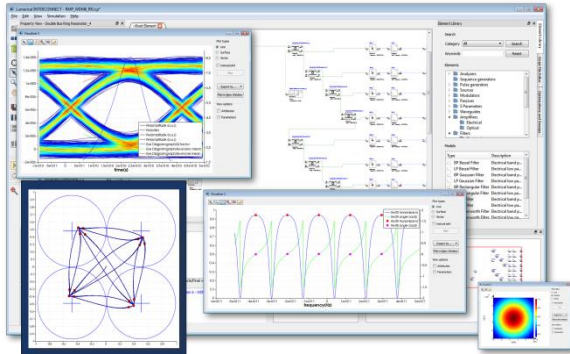
Compact Model  
Parameter Extraction

Optical Parameters Define  
Layout Structures

Photonic Component Design  
*Optoelectronic solvers,  
Experimental data*

*Lumerical  
Solutions*

*Phoenix  
Software*



Packaging by  
Chiral Photonics



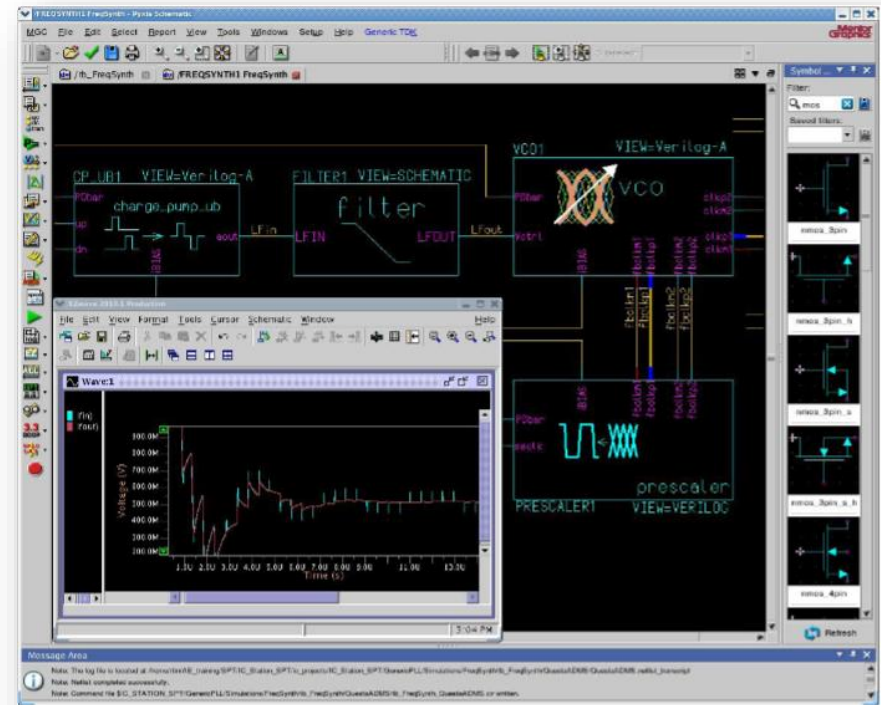
# Scaling photonics design

As in the electronic IC ecosystem, faster and more complex photonic ICs will require multi-user collaboration

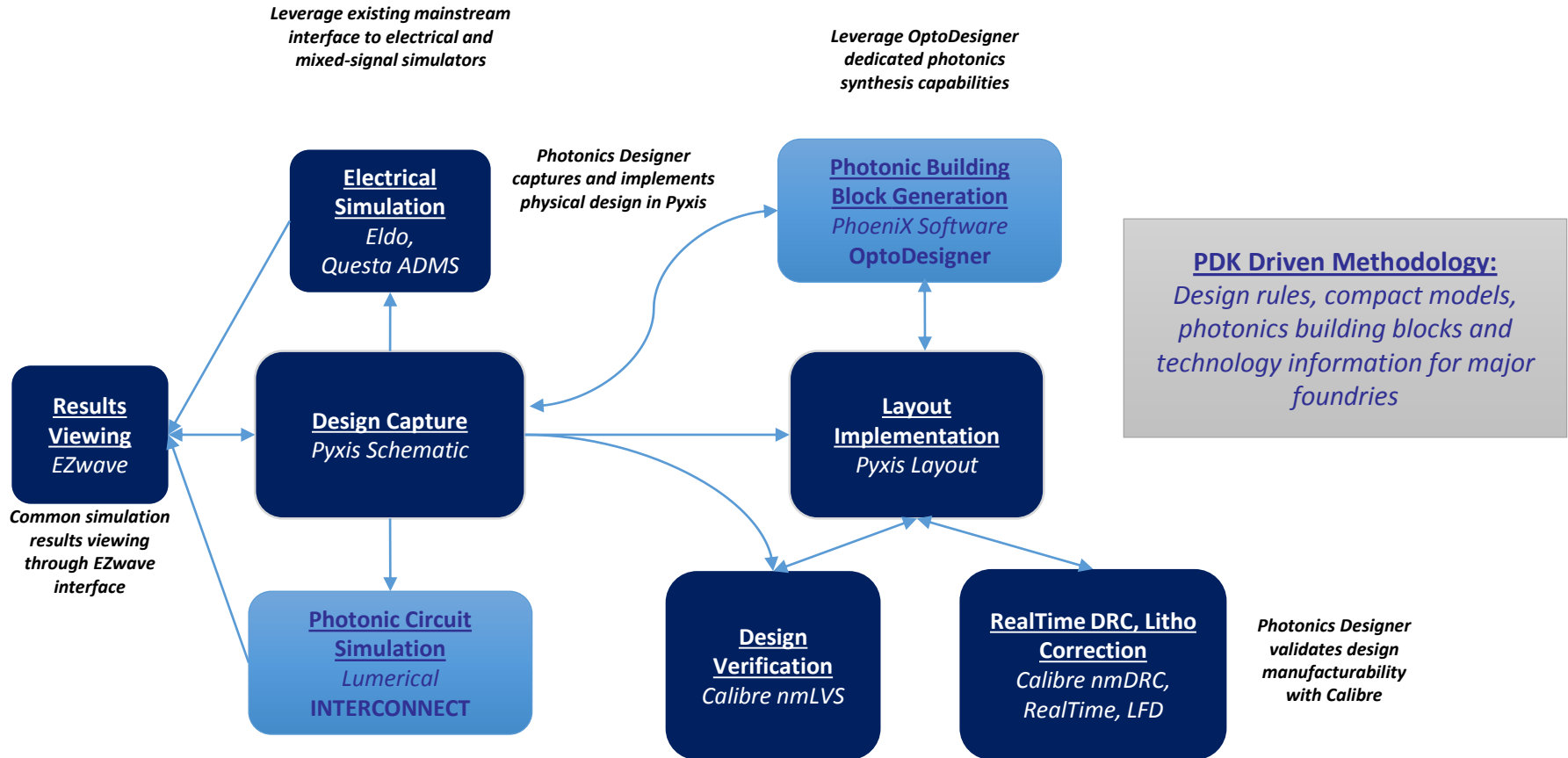
Innovators will need to build teams with dedicated expertise in multiple areas of PIC design – from system concept to physical layout

Mentor Graphics provides the tools to do this:

- Pyxis enables multi-user collaboration in common environment
- Calibre provides sign-off assurance through physical verification



# EDA Driven Design Flow

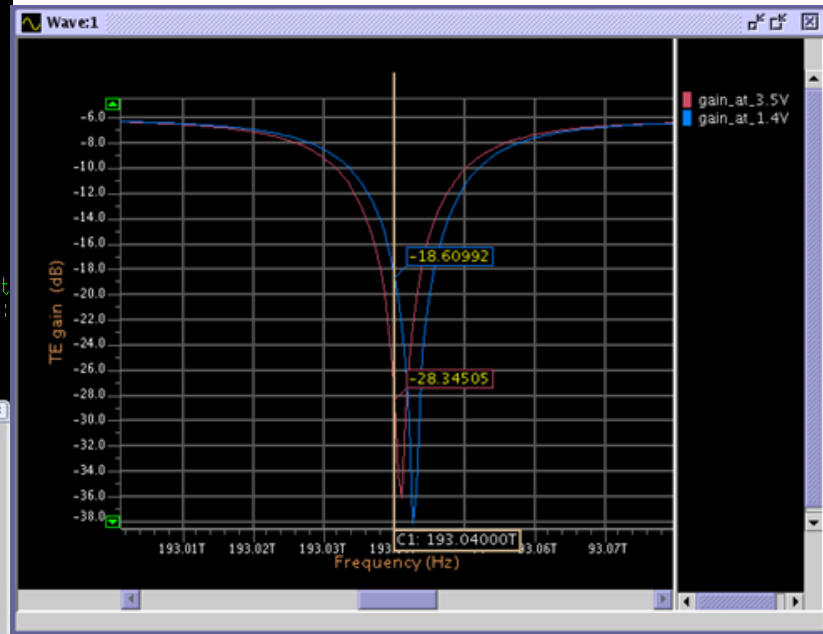
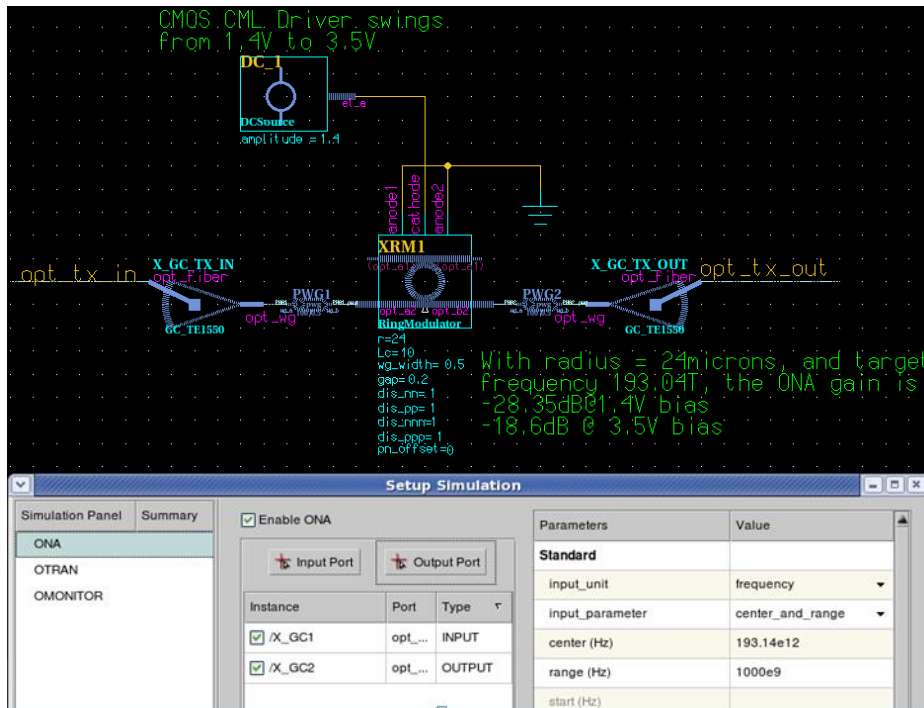


# Driving INTERCONNECT from Pyxis

## Schematic driven design and simulation

- Interactively setup sizing and DC biasing of modulators in *Pyxis* with *INTERCONNECT* ONA simulation
- View results in *EZwave* results viewer

Example: frequency domain spectral response



# Driving OptoDesigner from Pyxis

- Driving *OptoDesigner* from *Pyxis Schematic* and *Pyxis Layout* to calculate optical parameters and provide layout implementation

The screenshot displays the Pyxis software interface with several key components:

- Cell Selector:** A sidebar on the left showing a list of components like BondPad, GC\_PCell, GC\_TE150, GC\_TM1..., RingMod..., YBranch..., crossing1, phx\_spiral, and pn\_phase...
- Schematic View:** The main workspace shows a schematic diagram of an optical circuit. It includes components like GC\_TE1550, X\_GC2, PWG1, PWG2, PWG3, XPS1, XPS2, and a phx\_spiral component. Text annotations provide parameters such as 'time delay= 1.9p', 'wavelength= 1550n', 'waveguide\_type= STRIP', 'width= 0.5', and 'total\_length= 140.24'.
- Layer Palette:** A panel on the right showing a list of layers (Si, SiEtch1, SiEtch2, SiEtch3, DRCEXCLUDE, DEVREC, PINREC, fbrtgt, tp1, Text, bndtgt, OxEtch, N, P, Np, Pp, Npp, Ppp, GeN, GeP) with checkboxes for 'User Order' and 'Draw Order'.
- Edit Object Dialog:** A dialog box on the right showing the properties of a selected object. It has two sections:
 

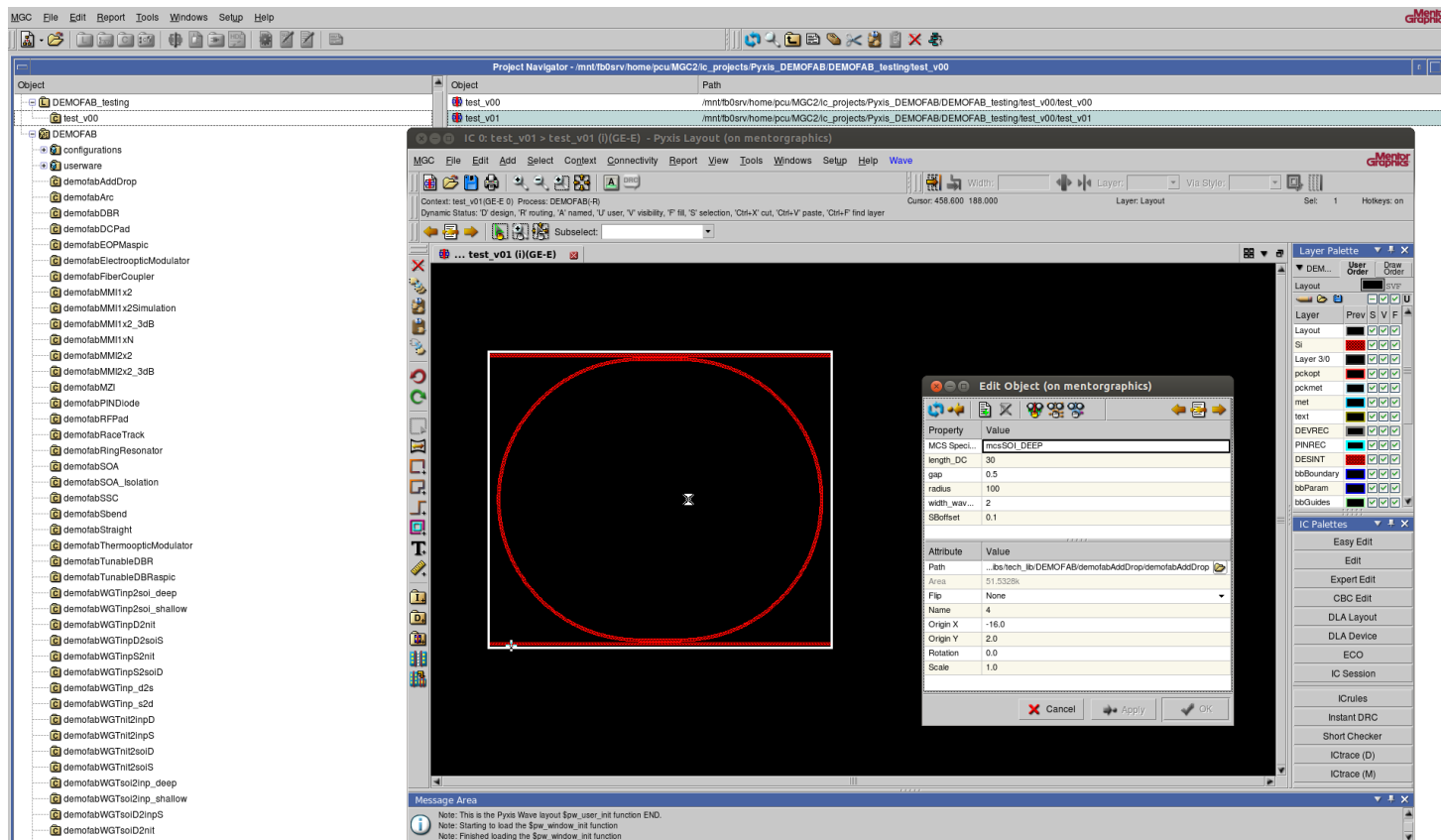
Property	Value
time_delay	80p
Wwavelength (m)	1550n
Waveguide Type	STRIP
Width (um)	0.5
Total length (um)	5.925406k
PhX output type	GDS
Run OptoDesigner	false

 and
 

Attribute	Value
Path	\$GSIP/GSIP/phx_spiral/phx_spiral
Area	43.716074716k
Flip	Horizontal
Name	/XPS2
Origin X	294.7
Origin Y	432.353
Rotation	0.0
Scale	1.0
- Notepad:** A text editor at the bottom showing the layout implementation code for the phx\_spiral component, including parameters like 'XPS2 PWG2\_PWG PWG3 phx\_spiral wg\_width=0.5 wg\_length=5.925406k wavelength=1550n'.

# Driving OptoDesigner from Pyxis

- All the design elements from *OptoDesigner* are provided in the *Pyxis* environment



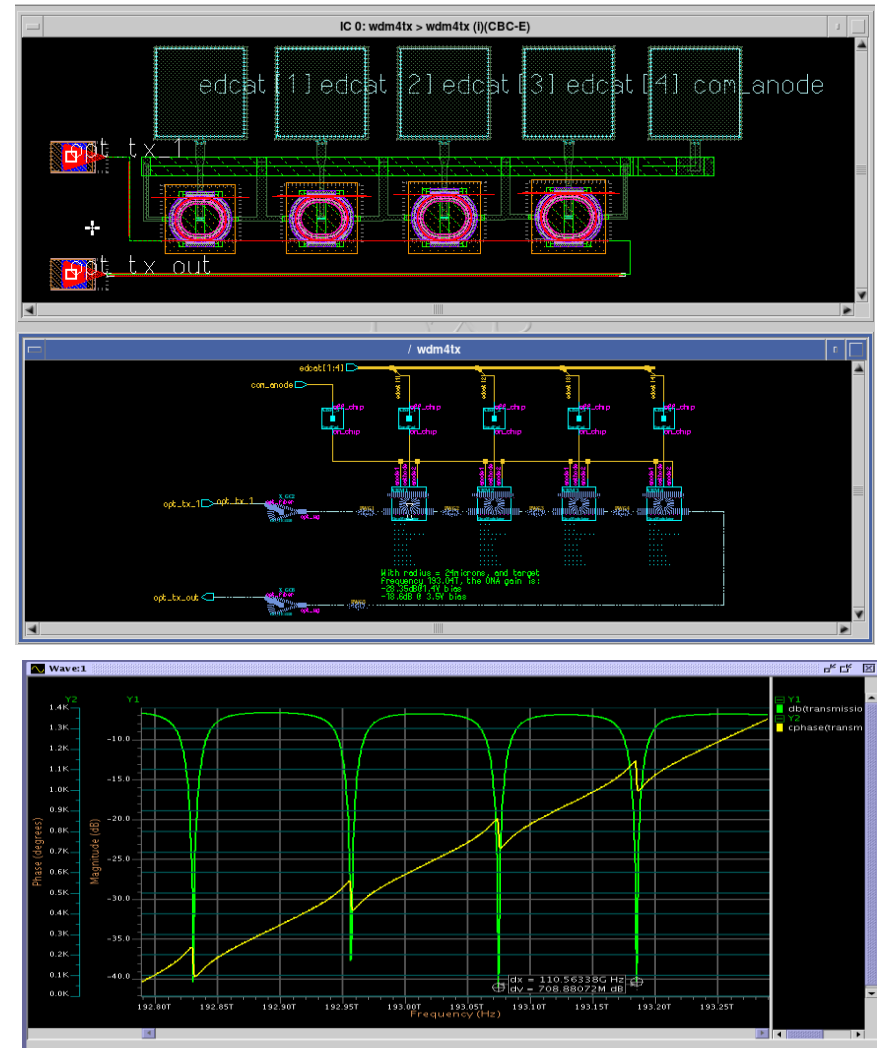
# Why Pyxis?

Provides a collaborative multi-user environment

Simulate schematics using Lumerical INTERCONNECT, Eldo with Verilog-A, or Questa ADMS

Flexible infrastructure allows quick integration to any tool accessible within Linux

Complete PDK driven design flow leveraging Calibre, Lumerical and Phoenix Software



# Why Calibre?

## Market and industry standard

### Fast and accurate DRC:

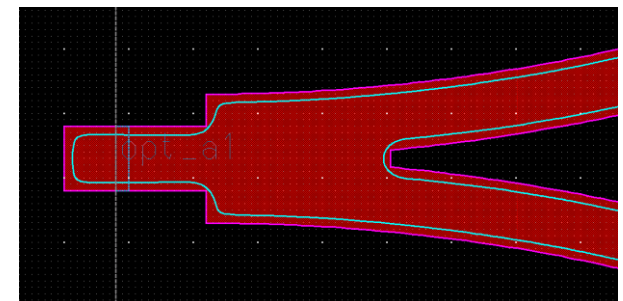
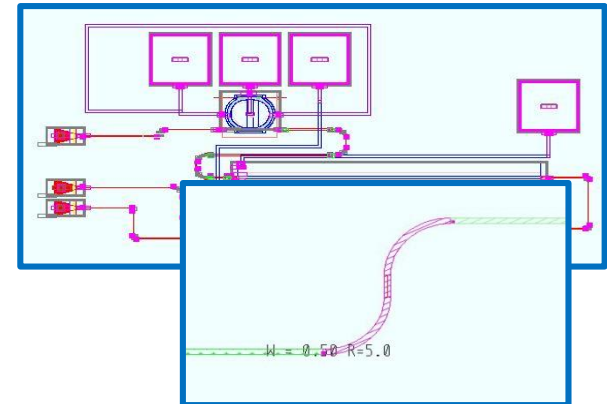
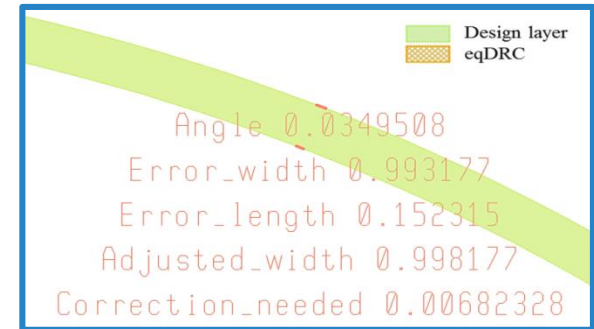
- EqDRC handles complex curves
- RealTime results in Pyxis

### Photonic LVS:

- Shorts & opens detection
- Device validation
- Waveguide interconnect parameter extraction

### Lithographic Modeling:

- Reduces manufacture iterations
- Drive accurate photonic simulation



# Why Lumerical?



## Three Distinct Design Activities for PIC Development

1. **Component-level design and optimization**
  - Design and optimize a component for desired performance
2. **Compact model library generation for PDKs**
  - Build compact model for component
  - Calibrate against experimental results
  - Inform with simulation results
3. **Photonic Integrated Circuit design and optimization**
  - Build complex circuits based on known components with validated compact models

User /  
Designer

User /  
Designer

Access  
Partners

Fabrication  
Packaging

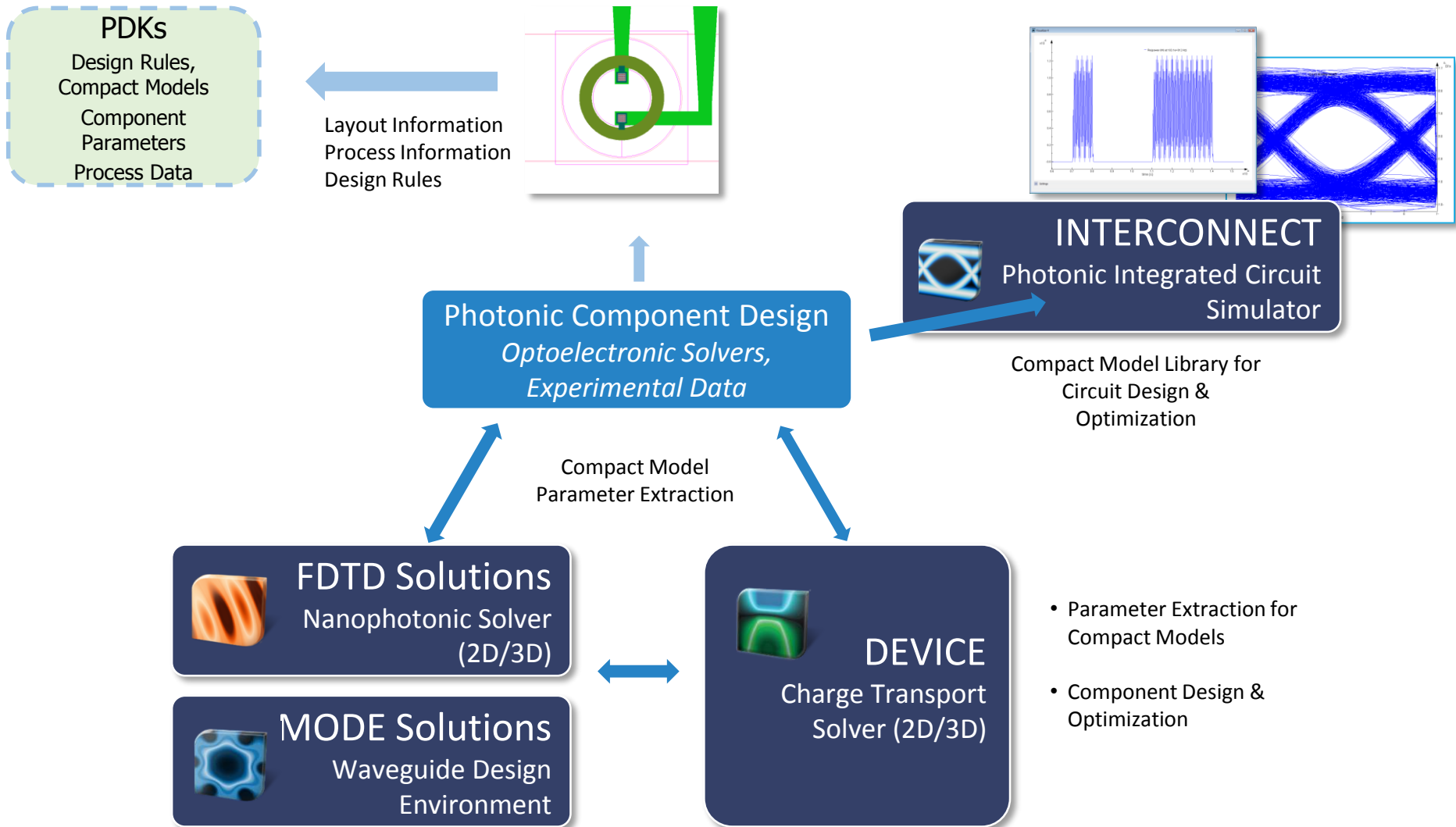
User /  
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# Why Lumerical?



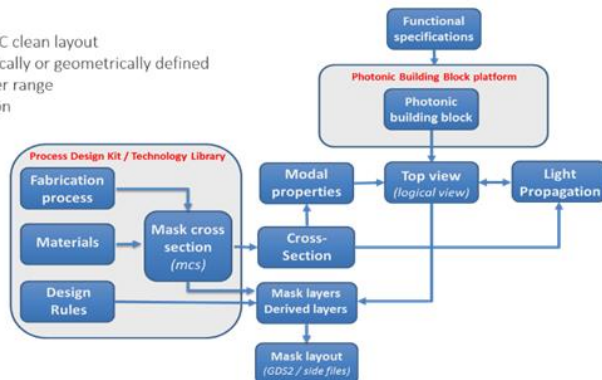
# Why Phoenix Software?

- Focus on Design for Manufacturability
- We have been supporting 100's of designers (MPW-users and at vertically integrated organizations) getting started with PIC design
- More than 25 years photonics design and tools expertise, available through excellent customer support
  - Our support is valued by our customers with a 9.1 out of 10

## 'Ease of design' through Photonic Synthesis

Photonic Building Block platform:

- Translates design intent into DRC clean layout
- Design intent can be either optically or geometrically defined
- Ability to handle wide parameter range
- Incorporates process information



## Photonic Building Blocks

- Match photonic specifications with foundry capabilities

BrightAWG module

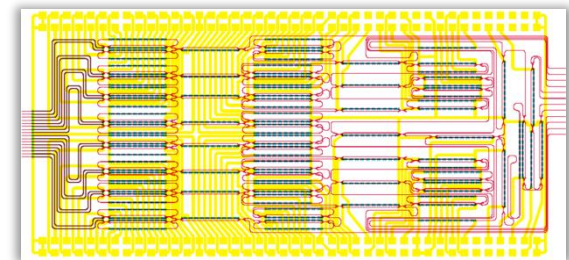
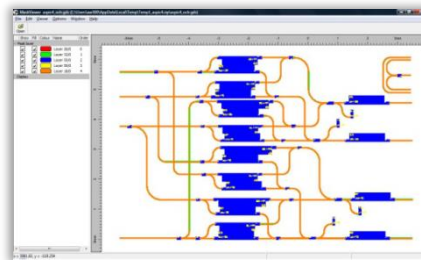
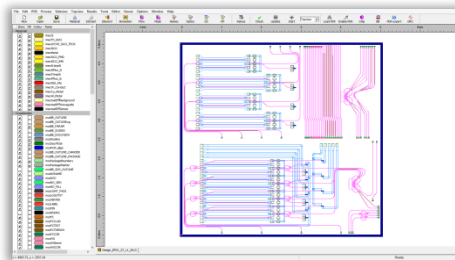
OCLARO

Fraunhofer  
Research Center Institute

# Why OptoDesigner?

- Native all-angle and all-shape design
- Complete parametrized library for photonics
- Includes photonics verification and design rule checking
- Interfaces with world-class 3<sup>rd</sup> party circuit simulators
- Enables EDA centric design flows
- Easy to use GUI including powerful scripting
- PDKs available for 8 photonics foundry services

More than 300 designs created and fabricated in MPW's in the last 3 years!



# Further Information

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[www.lumerical.com](http://www.lumerical.com)

More material including demo movies for the EDA-style design flow:  
[www.lumerical.com/tcad-products/interconnect/pyxis\\_eda/](http://www.lumerical.com/tcad-products/interconnect/pyxis_eda/)

And for the INTERCONNECT – OptoDesigner interface: [www.lumerical.com/phoenix/](http://www.lumerical.com/phoenix/)

[www.mentor.com](http://www.mentor.com)

A generic, non-proprietary silicon photonics design kit is available for download at  
[www.siepic.ubc.ca/GSiP](http://www.siepic.ubc.ca/GSiP)

[www.phoenixbv.com/optodesigner](http://www.phoenixbv.com/optodesigner)

Overview of available PDKs: [www.phoenixbv.com/designkits](http://www.phoenixbv.com/designkits)

